



IIT Bombay Nanofabrication Facility

Tool Name: Microwriter ML 3

Training and Usage Policy

Version 3.0

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Training & Usage Policy:

1. All IITBNF users can send training requests for authorization. Training and authorization process must be completed within 21 days.
2. At a time, max 3 active trainees will be allowed and other user's training requests will be kept in queue on a first come first serve basis.
3. Minimum 3 eyes-on and 3 hands-on training sessions are required before the authorization test.
4. AUs will be assigned training responsibilities as per the training needs. In addition, AUs may be asked to do process runs for others (in case of non-availability of operators).
5. Authorized users are expected to take care of process runs of other users from the same group.
6. Maximum 3 hours per slot and maximum 3 slots per user per week will be allowed.
7. Allowed minimum and maximum Feature sizes (line/space) : 2 μm (min) and 50 μm (max) for mask writing and 1 μm (min) and 50 μm (max) for direct writing.
8. The design (.cif) should be checked and approved by the system owner/operator. After approval, the design should be burned in a disk and submitted to the operator at least 24 hours before the slot.
9. The writing area of the design should be 2"X 2" for a 3 inch mask plate and 4" X 4" for a 5" mask plate. The design should be within the wafer outline boundary. The user should be ready to modify their design according to our parameters.
10. The mask plate issue request should be submitted. This is available in the online module in CEN website. The request should be approved by the guide. Without online approval, mask cannot be written.
11. The etching of the mask plate will be conducted once in a week. User should send a mail with Guide approval if they want the mask plate urgently.